

Electronic Patent Application Fee Transmittal

Application Number:	10591718			
Filing Date:	05-Sep-2006			
Title of Invention:	Positive-type resist composition for liquid immersion lithography and method for forming resist pattern			
First Named Inventor/Applicant Name:	Keita Ishiduka			
Filer:	Julie Tabarovsky/Marcy Mancuso			
Attorney Docket Number:	1608-7 PCT/US			
Filed as Large Entity				
U.S. National Stage under 35 USC 371 Filing Fees				
Description	Fee Code	Quantity	Amount	Sub-Total in USD(\$)
Basic Filing:				
Pages:				
Claims:				
Miscellaneous-Filing:				
Petition:				
Patent-Appeals-and-Interference:				
Post-Allowance-and-Post-Issuance:				
Extension-of-Time:				
Extension - 3 months with \$0 paid	1253	1	1270	1270

Description	Fee Code	Quantity	Amount	Sub-Total in USD(\$)
Miscellaneous:				
Request for continued examination	1801	1	930	930
Total in USD (\$)				2200